



K. Memory (Design & Process Technology) 분과

2021년 1월 28일(목), 13:00-14:30 / 채널 D

[TD3-K] Devices for Neuromorphic Computing II

좌장: 권용우 교수 (홍익대학교), 김형진 교수 (인하대학교)

<p>TD3-K-1 13:00-13:30</p>	<p>[초청] Device and Selector Optimization of Vertical RRAM and Its Application for Neuromorphic Computing</p> <p>Batyrbek Alimkhanuly, Arman Kadyrov, Yongsu Choi, and Seunghyun Lee <i>Department of Electronic Engineering, Kyung Hee University</i></p>
<p>TD3-K-2 13:30-13:45</p>	<p>Process-in-memory Performance Demonstration of Self-Rectifying Resistive Memory in an Integrated Crossbar Array</p> <p>Kanghyeok Jeon^{1,2}, Jin Joo Ryu¹, Seung-Jong Yoo^{1,2}, Min Kyu Yang³, Doo Seok Jeong², and Gun Hwan Kim¹ <i>¹Division of Advanced Materials, KRICT, ²Division of Materials Science and Engineering, Hanyang University, ³Department of Computer Car Mechatronics, Sahmyook University</i></p>
<p>TD3-K-3 13:45-14:00</p>	<p>Artificial Van-der-Waals Hybrid Synapse for Brain-Inspired Parallel Computing</p> <p>Seunghwan Seo¹ and Jin-Hong Park^{1,2} <i>¹Department of Electrical and Computer Engineering, Sungkyunkwan University, ²Sungkyunkwan University Advanced Institute of Nanotechnology, Sungkyunkwan University</i></p>
<p>TD3-K-4 14:00-14:15</p>	<p>Short-term and Long-term Memory Operations of a-IGZO Synaptic TFTs with the Low-temperature ALD Al₂O₃ Gate Insulator and Metal Floating Gate</p> <p>Dongyeon Kang, Jun Tae Jang, Dong Myong Kim, Sung-Jin Choi, Jong-Ho Bae, and Dae Hwan Kim <i>School of Electrical Engineering, Kookmin University</i></p>
<p>TD3-K-5 14:15-14:30</p>	<p>Atomic Layer Chemical Vapor Deposition of SiO₂ Thin Film Using Chlorine-free Silicon Precursor for 3D NAND Application</p> <p>Ji-hoon Baek¹, GeonHo Baek², Hye-mi Kim¹, Seunghwan Lee¹, Yusung Jin³, Hyung Soon Park³, Deok-Sin Kil³, Sangho Kim⁴, Yongjoo Park⁴, and Jin-Seong Park^{1,2} <i>¹Division of Materials Science and Engineering, Hanyang University, ²Division of Nanoscale Semiconductor Engineering, Hanyang University, ³Materials Development White Team, SK Hynix Inc., ⁴Advanced Research Development Team, SK Trichem Co., Ltd.</i></p>